

APPARATUS FOR TREATING GASEOUS POLLUTANTS

Abstract

Provided is an apparatus for treating gaseous pollutants,
5 including a gas inlet part, a first treatment unit, a second treatment
unit and a non-mechanical flow-guiding device. The gas inlet part
includes a gas inlet chamber and at least one guide pipe. The guide
pipe communicates with the gas inlet chamber and guides an effluent
stream from a semiconductor process to the gas inlet chamber. The
10 first treatment unit is coupled to a bottom end of the gas inlet part
and is configured to abate the effluent stream. The non-mechanical
flow-guiding device is coupled to the first treatment unit. The flow-
guiding device is configured to guide the effluent stream to move
toward an opening. The second treatment unit is coupled to the flow-
15 guiding device via the opening, receives the effluent stream from the
first treatment unit and further abates the effluent stream.

FIG. 2B